

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1742		SERIAL NO. 09/943,187	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Kristy A. Campbell et al.			
				FILING DATE August 29, 2001		GROUP 2822	
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
KBD	AA	3,622,319	11/23/71	Sharp	96	27	
	AB	3,743,847	07/03/73	Boland	250	510	
	AC	4,269,935	05/26/81	Masters et al.	430	323	
	AD	4,312,938	01/26/82	Drexler et al.	430	496	
	AE	4,320,191	03/16/82	Yoshikawa et al.	430	296	
	AF	4,795,657	01/03/89	Formigoni et al.	427	96	
	AG	4,847,674	07/11/89	Silwa et al.	357	67	
	AH	5,177,567	01/05/93	Klersy et al.	257	4	
	AI	5,219,788	06/15/93	Abernathy et al.	437	187	
	AJ	5,726,083	03/10/98	Takaishi	438	210	
✓	AK	5,751,012	05/12/98	Wolstenholme et al.	257	5	
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes No
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
KBD	AN		Das et al., <i>Theory of the characteristic curves of the silver chalcogenide glass inorganic photoresists</i> , 54 APPL. PHYS. LETT., No. 18, pp. 1745-1747 (May 1989).				
	AO		Helbert et al., <i>Intralevel hybrid resist process with submicron capability</i> , SPIE Vol. 333				
			SUBMICRON LITHOGRAPHY pp. 24-29 (1982)				
↓	AP		Hilt, DISSERTATION: <i>Materials Characterization of Silver Chalcogenide Programmable Metallization</i>				
			Cells, Arizona State University, pp. title page-114 (UMI Company, May 1999).				
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[Signature]				11/25/02			
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KBD	AA	5,789,277	08/04/98	Zahorik et al.	438	95	
	AB	5,841,150	11/24/98	Gonzalez et al.	257	3	
	AC	5,920,788	07/06/99	Reinberg	438	466	
	AD	5,998,066	12/07/99	Block et al.	430	5	
	AE	6,077,729	06/20/00	Harshfield	438	128	
	AF	6,236,059 B1	05/22/01	Wolstenholme et al.	257	3	
	AG	6,297,170 B1	10/02/01	Gabriel et al.	438	738	
	AH	6,300,684 B1	10/09/01	Gonzalez et al.	257	774	
	AI	6,316,784 B1	11/13/01	Zahorik et al.	257	3	
	AJ	6,329,606 B1	12/11/01	Freyman et al.	174	260	
	AK	6,348,365	02/19/02	Moore et al.	438	130	

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KBD	AN		Holmquist et al., <i>Reaction and Diffusion in Silver-Arsenic Chalcogenide Glass Systems</i> , 62 J. AMER. CERAMIC SOC., Nos. 3-4, pp. 183-188 (Mar.-Apr. 1979).
	AO		Huggett et al., <i>Development of silver sensitized germanium selenide photoresist by reactive sputter etching in SF₆</i> , 42 APPL. PHYS. LETT., No. 7, pp. 592-594 (April 1983).
	AP		Kawaguchi et al., <i>Mechanism of photosurface deposition</i> , 164-166 J. NON-CRYST. SOLIDS, pp. 1231-1234 (1993).

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KBD	AA	6,376,284 B1	04/23/02	Gonzalez et al.	438	129	
	AB	6,391,688 B1	05/21/02	Gonzalez et al.	438	128	
	AC	6,414,376 B1	07/02/02	Thakur et al.	257	640	
	AD	6,418,049 B1	07/09/02	Kozicki et al.	365	174	
	AE	6,423,628 B1	07/23/02	Li et al.	438	622	
	AF						
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KBD	AN	McHardy et al., <i>The dissolution of metals in amorphous chalcogenides and the effects of electron and ultraviolet radiation</i> , 20 J. PHYS. C: SOLID STATE PHYS., pp. 4055-4075 (1987).
	AO	Miyatani, <i>Electrical Properties of Ag₂Se</i> , 13 J. Phys. Soc. Japan, p. 317 (1958).
	AP	Mizusaki et al. <i>Kinetic Studies on the Selenization of Silver</i> , 47 BUL. CHEM. SOC. JAPAN., No. 11 pp. 2851-2855 (November 1974).

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KBD	AA	10/077,867		Campbell et al. (as filed)			02/20/2002
↓	AB	10/232,757		Li, et al. (as filed)			08/29/2002
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KBD	AN	Owen et al., <i>Metal-Chalcogenide Photoresists for High Resolution Lithography and Sub-Micron Structures</i> , NANOSTRUCTURE PHYSICS AND FABRICATION, pp. 447-451 (Academic Press, 1989).
↓	AO	Safran et al., <i>TEM study of Ag₂Se developed by the reaction of polycrystalline silver films and selenium</i> , 317 THIN SOLID FILMS, pp. 72-76 (1998).
↓	AP	Shimizu et al., <i>The Photo-Erasable Memory Switching Effect of Ag Photo-Doped Chalcogenide Glasses</i> , 46 BUL. CHEM. SOC. JAPAN, No. 12, pp. 3662-3665 (December 1973).

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	AN		Somogyi et al., <i>Temperature Dependence of the Carrier Mobility in Ag₂Se Layers Grown on NaCl and SiO_x Substrates</i> , 74 ACTA PHYSICA HUNGARICA, No. 3, pp. 243-255 (1994).			
	AO		Tai et al., <i>Multilevel Ge-Se film based resist systems</i> , SPIE Vol. 333 SUBMICRON LITHOGRAPHY, pp. 32-39 (March 1982).			
	AP		Tai et al., <i>Submicron optical lithography using an inorganic resist/polymer bilevel scheme</i> , 17 J. Vac. Sci. Technol., No. 5, pp. 1169-1176 (Sept./Oct. 1980).			
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	AN		West, DISSERTATION: <i>Electrically Erasable Non-Volatile Memory Via electrochemical Deposition of Multifractal Aggregates</i> , Arizona State University, pp. title page-168 (UMI Co., May 1998).				
	AO		West et al., <i>Equivalent Circuit Modeling of the Ag As_{0.24}S_{0.36}Ag_{0.40} Ag System Prepared by Photodissolution of Ag</i> , 145 J. Electrochem. Soc., No. 9, pp. 2971-2974 (September 1998).				
	AP		Yoshikawa et al., <i>A new inorganic electron resist of high contrast</i> , 31 APPL. PHYS. LETT., No. 3, pp. 161-163 (August 1977).				
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MBD	AN		Yoshikawa et al., <i>Dry development of Se-Ge Inorganic photoresist</i> , 36 APPL. PHYS. LETT., No. 1, pp. 107-109 (January 1980).				
	AO						
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